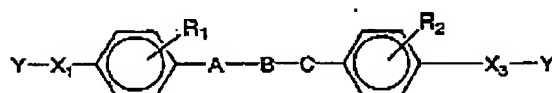


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Amendments to the Claims:

Claims 1 – 14 (Cancelled)

15. (Previously Presented) A photosensitive composition for optical waveguides comprising an organic oligomer and a polymerization initiator, said organic oligomer being an oligomer represented by the following formula (5a):



(5a)

wherein R₁ and R₂ may be the same as or different from each other, and denote hydrogen, halogen, an alkyl group, an alkoxy group or a trifluoromethyl group; X₁, and X₃ may be the same as or different from each other, and denote a connection group including at least one selected from the group consisting of an alkyleneoxy and oxyalkylene group; Y denotes a polymerization activating group containing acrylic or methacrylic group and A denotes a connection group selected from a linear or branched alkylene group; B denotes a connection group selected from the group consisting of a substituted or an unsubstituted phenylene; C denotes a connection group selected from alkyleneoxy.

16. (Canceled)

17. (Original) A method of forming a polymer optical waveguide pattern, comprising the steps of:

applying and drying a photosensitive composition for optical waveguides;
irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and

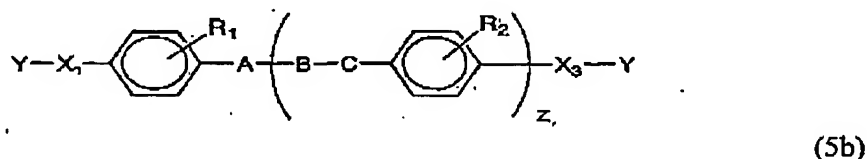
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directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides as claimed in Claim 15 is used as said photosensitive composition for optical waveguides.

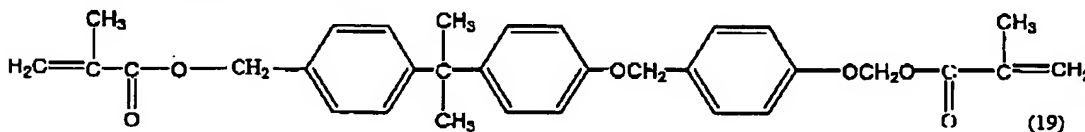
Claims 18-20 (Cancelled)

21. (Previously Presented) A photosensitive composition for optical waveguides comprising an organic oligomer and a polymerization initiator, said organic oligomer being an oligomer represented by the following formula (5b):



wherein R_1 and R_2 may be the same as or different from each other, and denote hydrogen, halogen, an alkyl group, an alkoxy group or a trifluoromethyl group; X_1 and X_3 may be the same as or different from each other, and denote a connection group including at least one selected from the group consisting of an alkyleneoxy and oxyalkylene group; Y denotes a polymerization activating group containing an epoxy group and A denotes a connection group selected from a linear or branched alkylene group; B denotes a connection group selected from a substituted or an unsubstituted oxyalkylene; C denotes a connection group selected from oxyalkylene, said oxyalkylene of B and said alkyleneoxy C including at least one OH group; and $z = 1$ or 2 .

22. (Previously Presented) A photosensitive composition for optical waveguides comprising an organic oligomer and a polymerization initiator, said organic oligomer represented by the following formula (19):



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Claims 23 – 26 (Cancelled)

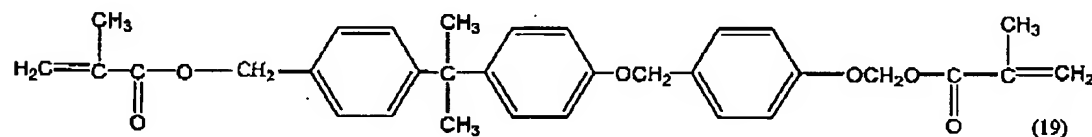
27. (Previously Presented) A method of forming a polymer optical waveguide pattern comprising the steps of:

applying and drying a photosensitive composition for optical waveguides;

irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and

directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides has the following formula (19):



28. (Previously Presented) A method of forming a polymer optical waveguide pattern, comprising the steps of:

applying and drying a photosensitive composition for optical waveguides;

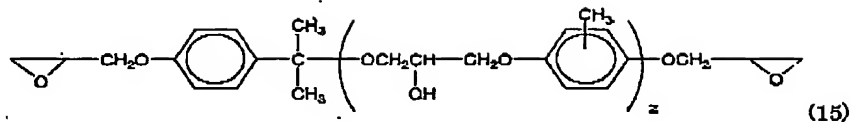
irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and

directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides as claimed in Claim 21 is used as said photosensitive composition for optical waveguides.

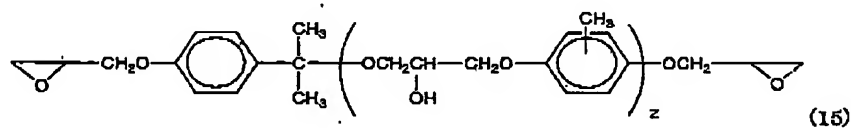
29. (Previously Presented) The photosensitive composition for optical waveguides claimed in claim 21, wherein said organic oligomer is selected from the compound having following formula (15):

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wherein $z = 1$ or 2 .

30. (Currently Amended) The method of forming a polymer optical waveguide pattern as claimed in claim 28, wherein said organic oligomer is selected from the compound having following formula (15):



wherein $z = 1$ or 2 .